

# 集成电路自动化设计方法

## (Design Automation of VLSI)

### 2015-秋季学期

电子科学与技术系：陈 松

2015年9月10日

Course Webpage:

<http://staff.ustc.edu.cn/~songch/da-ug.htm>



# Terminologies

- EDA (Electronic Design Automation)
  - 电子设计自动化
  - Synopsys, Cadence, Mentor Graphics, Agilent, etc.
- VLSI CAD (Very Large Scale Integration Computer-aided Design)
  - 超大规模集成电路计算机辅助设计
- IC CAD (Integrated Circuit Computer-aided Design)
  - 集成电路计算机辅助设计



# Outline

- Course Overview
  - Contents
  - Evaluation
  - Course information
- History of Integrated Circuits



# Course Info

- Name: Design Automation of VLSI (集成电路自动化设计方法)
  - Teacher: 陈松 [songch@ustc.edu.cn](mailto:songch@ustc.edu.cn), 3A303, Thursday 3,4
    - Tel: 63602675    Mobile: 13155167790
  - Text books
    - **Lecture Notes**
    - Wang, Chang, and Cheng (Ed.), *Electronic Design Automation: Synthesis, Verification, and Test*, Morgan Kaufmann, 2009.
    - Meil H. E. Weste and David Money Narris, *CMOS VLSI Design: A circuits and Systems Perspective*, fourth edition, Addison-Wesley, 2011.
    - David A. Patterson and John L. Hennessy, **Computer Organization and Design: The hardware/software interface**, 4th edition, Appendix C, Chapter 3, Chapter 4.
- Available on the following webpage:
- <http://staff.ustc.edu.cn/~songch/da-ug.htm>



# What

- Design methodology
  - Standard Cell / IP (Intellectual Property), FPGA, PLA
- Design Metrics
  - Power, Performance, Area, etc.
- Logic Design (Logic Synthesis)
  - Front-end design: From RTL to Logic Gates
- Physical Design (Physical Synthesis, Layout)
  - Back-end design: From Gates to GDSII
- Labs (Begin at the third week)
  - Verilog Hardware Description Language Basics
  - Synopsys Tool Suits: vcs, design compiler/power compiler/primetime, ICC compiler



# Why

- EDA Tool Designers
  - Basic requirements
- Theoretical guide for problem solving in using VLSI design tools
- VLSI System Architecture Designers
  - Coupling the front-end design and back-end design to shorten the design cycle and improve the chip performance
    - **Complex multiplexer structures often cause congestion problem**



# Grading Policy

- Lecture Attendance: 10%
- Lab attendance: 50%
- Homework: 40%



# 提纲



## 集成电路



## Golden Moore & Von Neumann

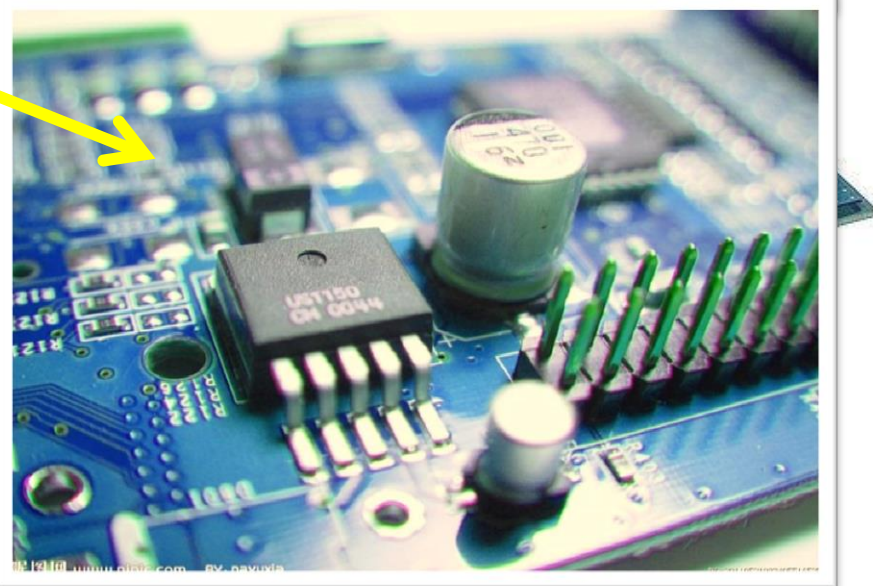
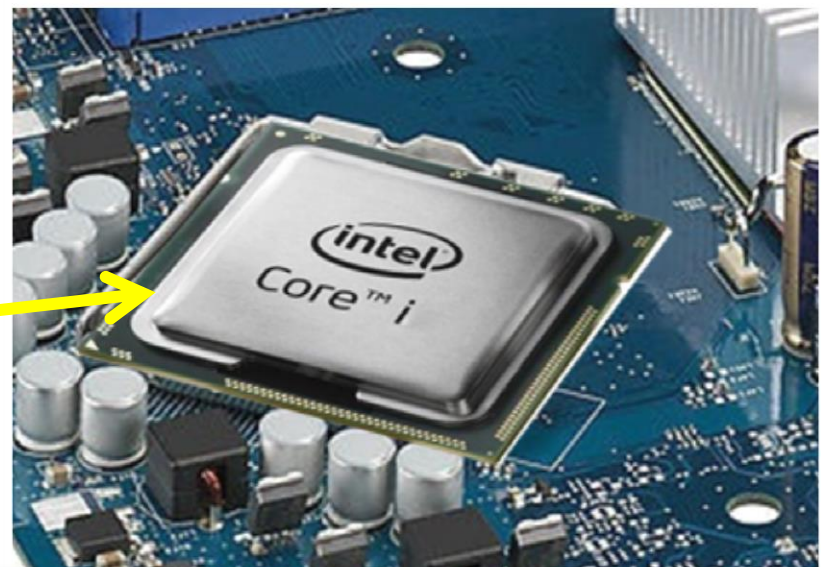
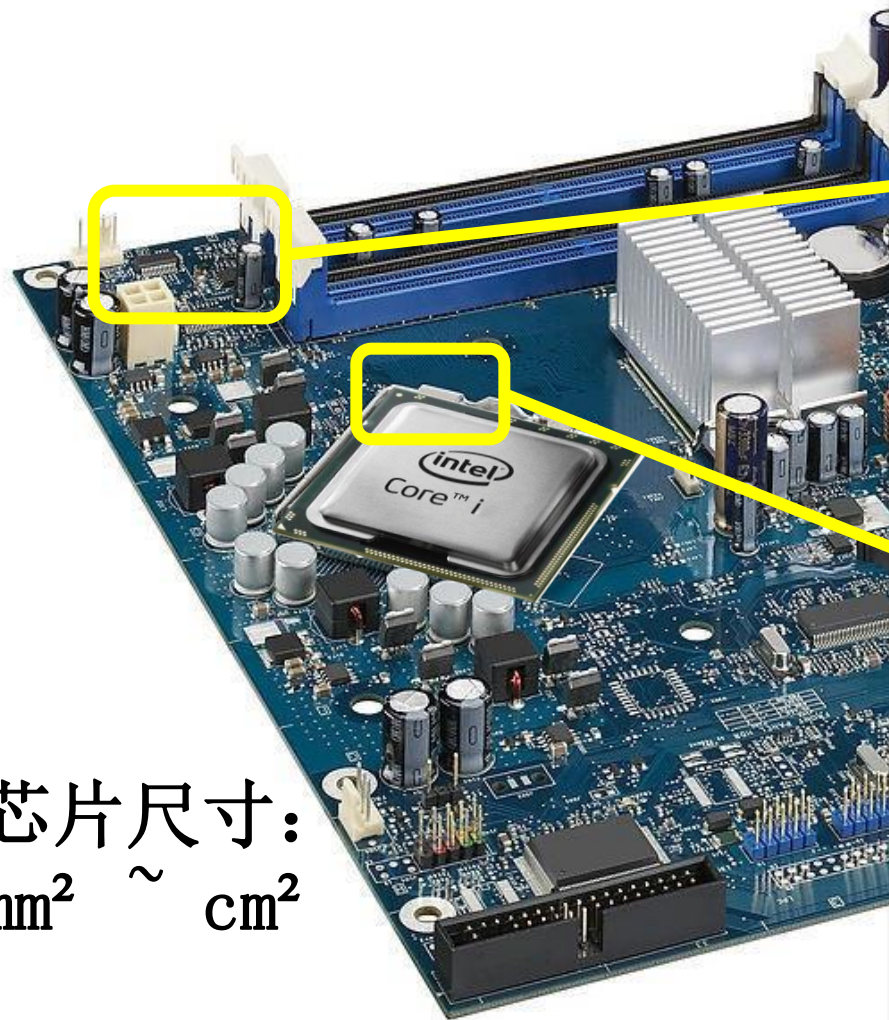


## 纳米电子时代的挑战



## 集成电路设计





芯片尺寸:  
 $\text{mm}^2 \sim \text{cm}^2$



# 晶体管



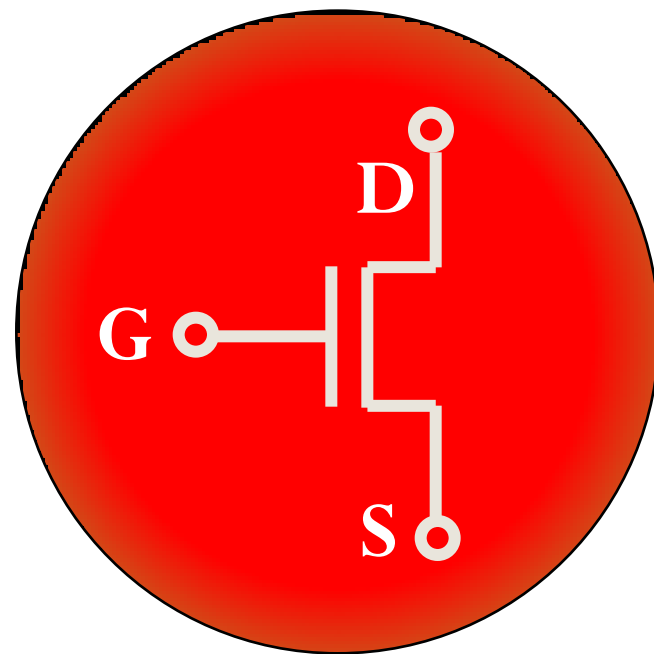
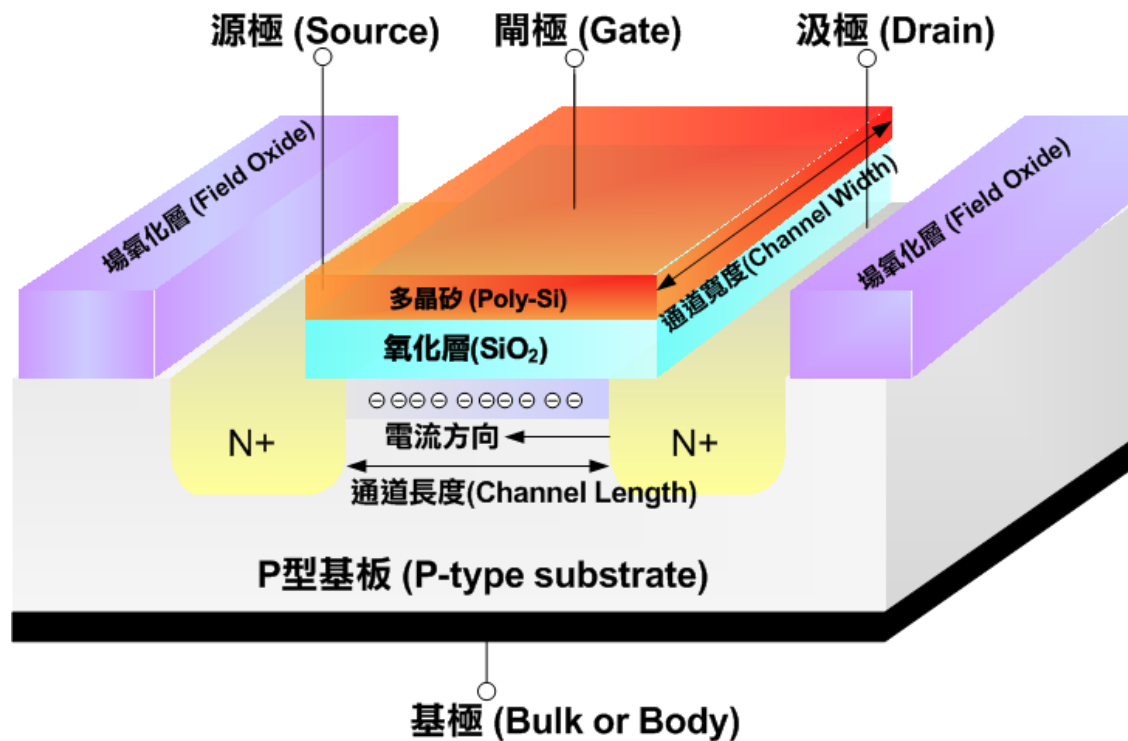
1947年，第一支晶体管在美国贝尔实验室诞生，**肖克利、巴丁和布拉顿**获得**1956年诺贝尔物理学奖**



W. Shockley, J. Bardeen and W. Brattain

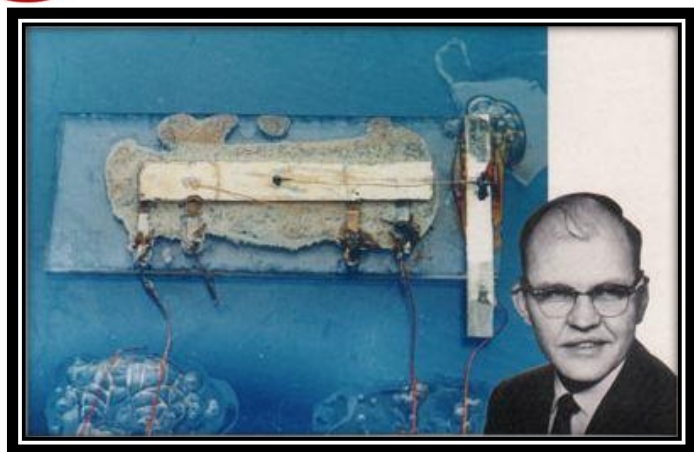


# 半导体晶体管

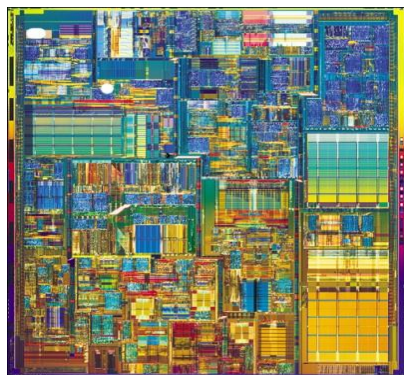


## 金属氧化物半导体晶体管 ( MOS晶体管 ) 结构图

# 集成电路

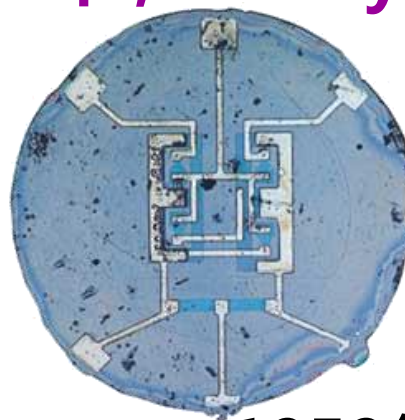


1958年，Jack S. Kilby  
发明了集成电路的雏型

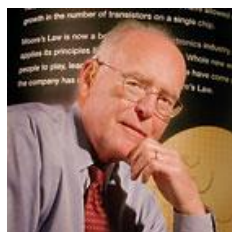


Pentium IV

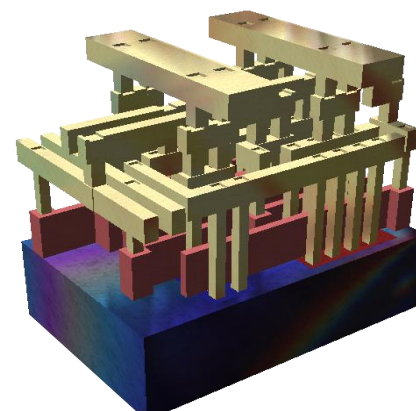
2000年，J. Kilby获得诺贝尔物理学奖



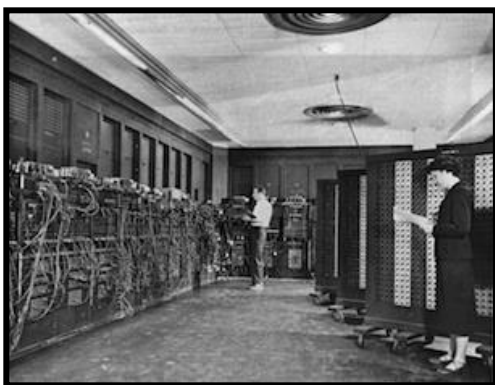
1959年，R. Noyce  
发明了今天的集成电路



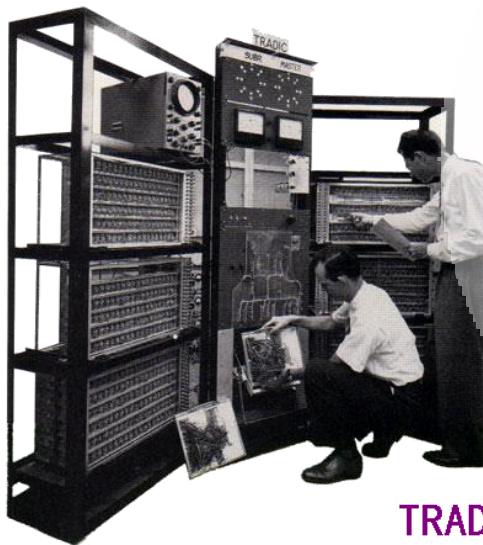
INTEGRAteD ELEctRONICS



# 计算机的演变



ENIAC: 1945年第一台电子计算机诞生, 它使用18000只电子管, 70000只电阻, 500万个焊点, 耗电160千瓦, 占地170平方米, 重30吨, 运算速度5000次/秒



TRADIC: 1954年第一台晶体管计算机在贝尔实验室诞生, 它使用800只晶体管



P4004: 1971年世界上第一个微处理器在英特尔公司诞生



IBM360: 1964年第一台集成电路计算机在IBM公司诞生, 共6个型号, 兼顾了科学计算和事务处理两方面的应用, 各种机器全都相互兼容。它的研制开发经费高达50亿美元, 是研制第一颗原子弹的曼哈顿计划的2.5倍。



# 提纲



## 集成电路



## Golden Moore & Von Neumann



## 纳米电子时代的挑战



## 集成电路设计



# 戈登·摩尔 和 约翰·冯·诺依曼

Golden Moore

按比例缩小



P4004: 1971年世界上第一个微处理器在英特尔公司诞生

半导体

Von Neumann



冯·诺依曼体系结构

计算机

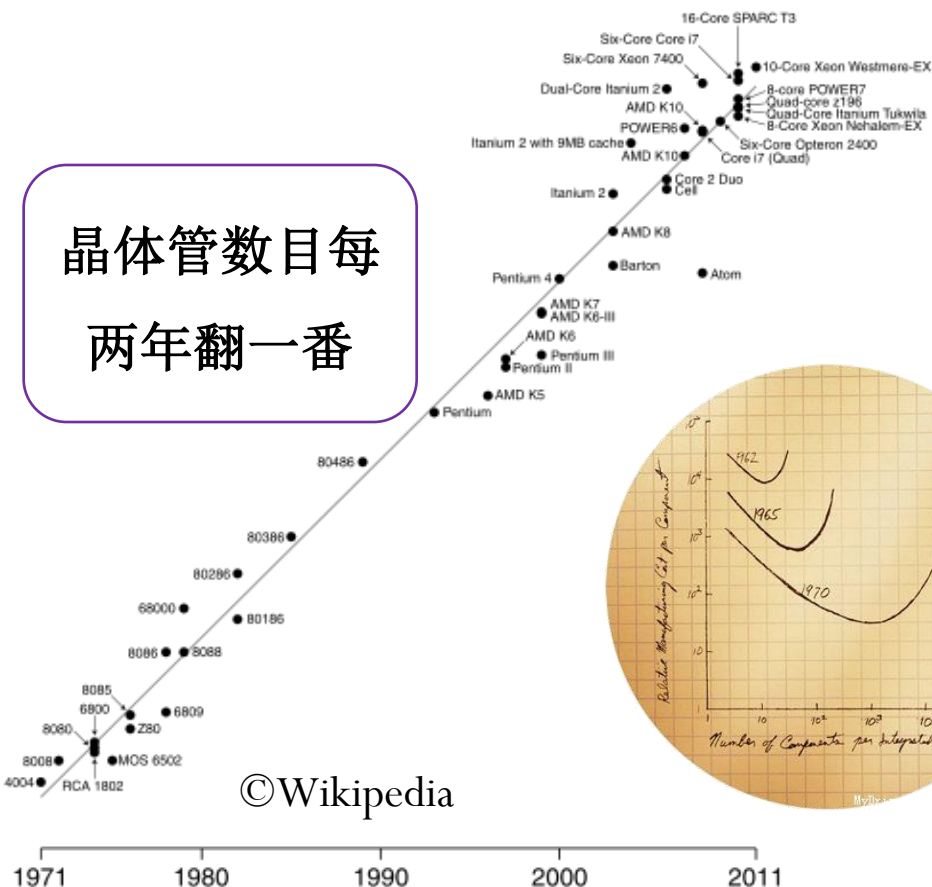


# 摩尔定律

Microprocessor Transistor Counts 1971-2011 & Moore's Law

晶体管数目

晶体管数目每  
两年翻一番



©Wikipedia

生产时间

to such we  
als connected to a  
or automobiles, a  
ipment. The elec  
be feasible today  
in the pro

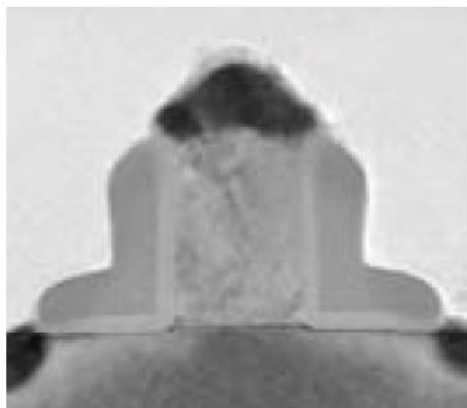
©Intel



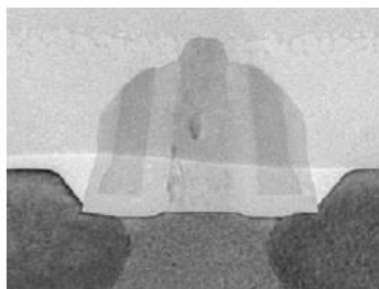


# 等比例缩小 (Scaling Down)

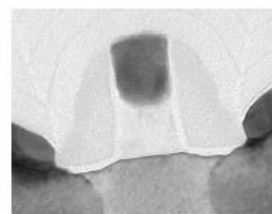
## 等比例缩小的半导体晶体管



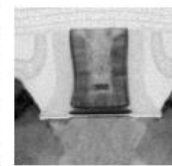
130nm



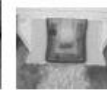
90nm



65nm



45nm



32nm

©Kelin, Intel

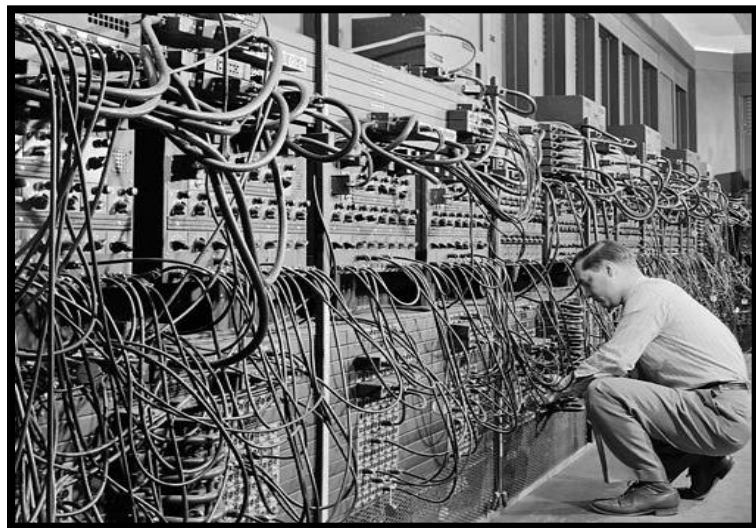
原因之一：按比例缩小 (Scaling Down)

- 等比例缩小是将一组硅器件的技术参数(通常多余20个)同步缩小
- 摩尔定律讲的是技术密度
- 摩尔定律是对集成电路产业的预测
- 等比例缩小是实现摩尔定律的方法



# ENIAC：专用计算机

原因之二：计算（Computation）



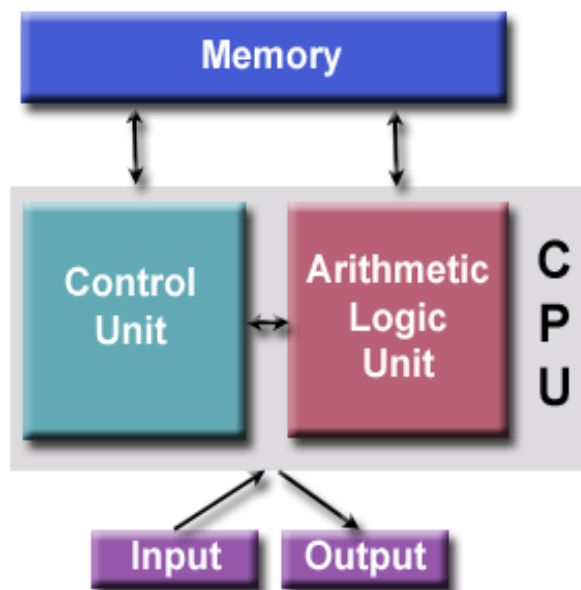
ENIAC运行时，安排了一批年轻的女性工作人员按照计算要求插拔众多的接头，以实现不同的运算。工作十分繁琐，出错概率很大，效率很低。硬件的准备时间大大超过实际的计算所需的时间。

ENIAC是一台专为美国军方计算火炮弹道轨迹设计的专用计算机。虽然具备一定的编程能力，但程序是事先预置好的。改变程序就要求工作人员改变硬件的连线结构。严格意义上讲，ENIAC不是一台通用计算机。



# 冯·诺依曼体系结构

原因之二：计算 (Computation)

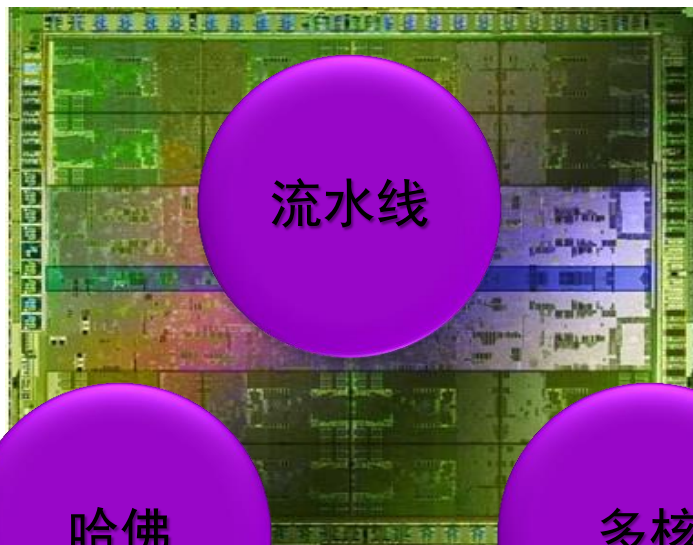


数字计算机的数制采用二进制；  
计算机应该按照程序顺序执行  
计算机：控制器、运算器、存储器、输入设备、输出设备；  
从ENIAC到当前最先进的计算机都采用的是冯诺依曼体系结构。

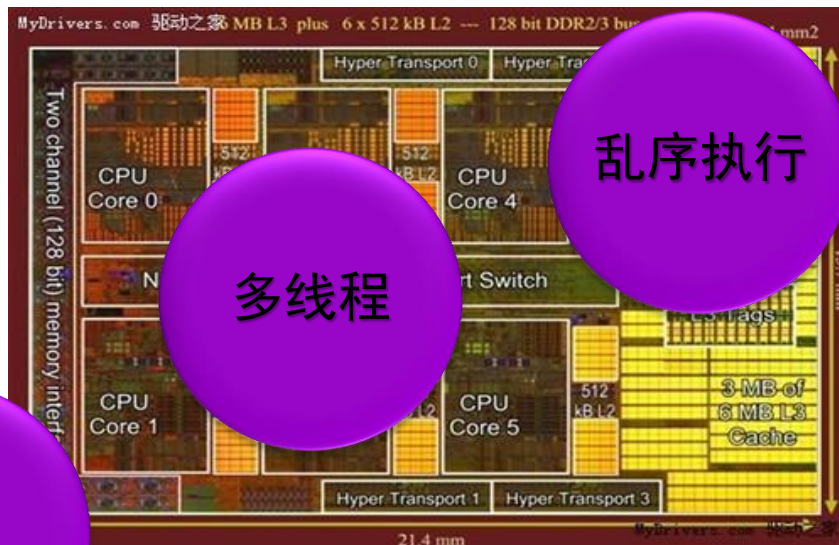


# 各种不同的体系结构

原因之二：计算 (Computation)



流水线



多线程

乱序执行



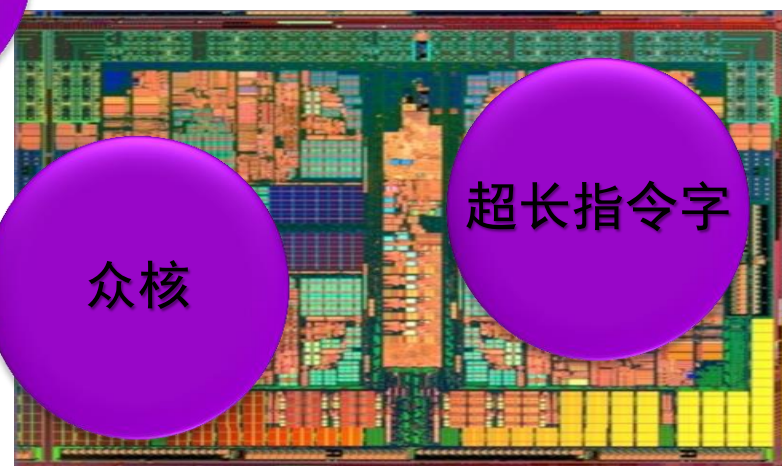
哈佛



多核



双核



众核

超长指令字





# 传统半导体行业



投资



晶体管按比例缩小

摩尔定律

性能更高  
成本更低

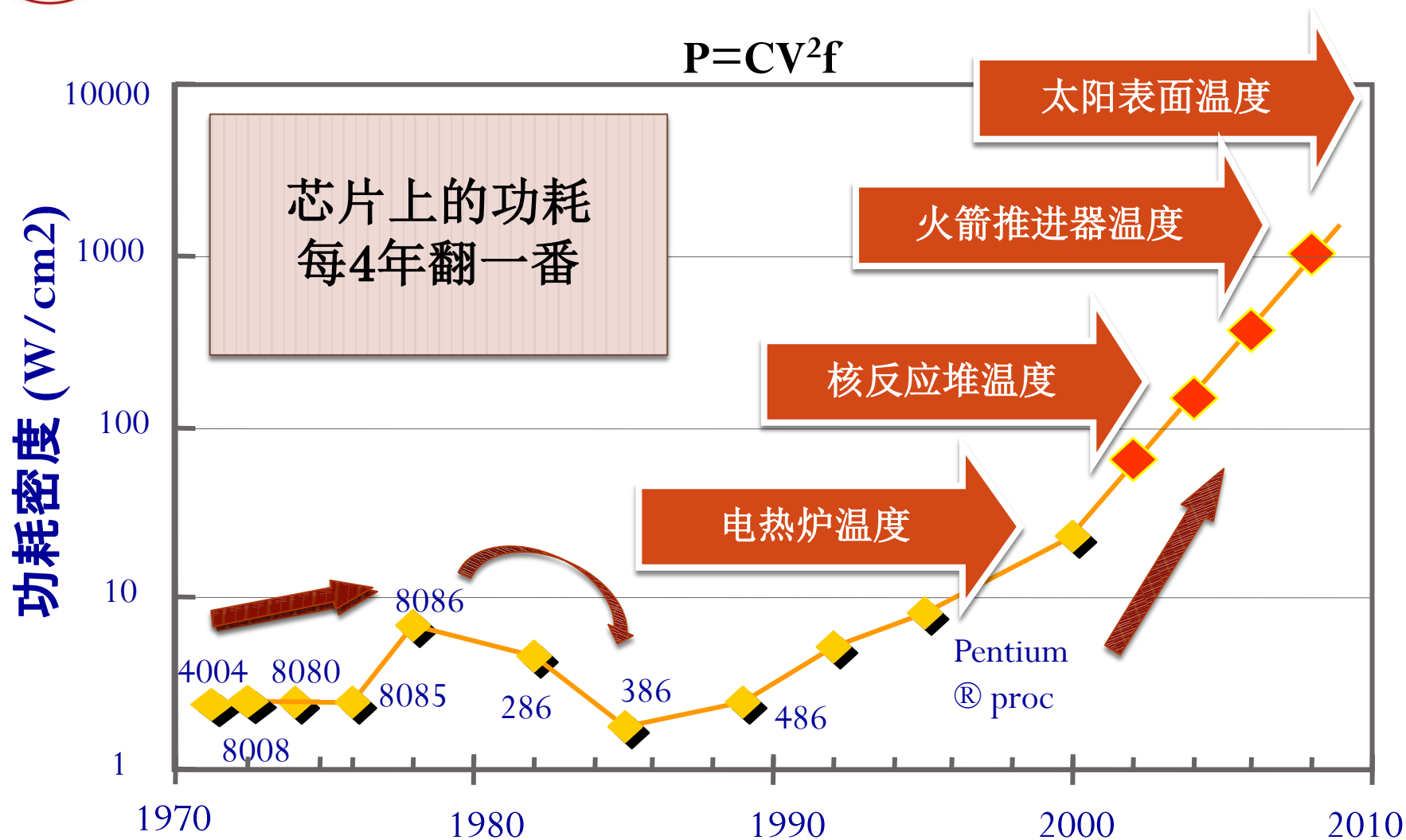


市场增长

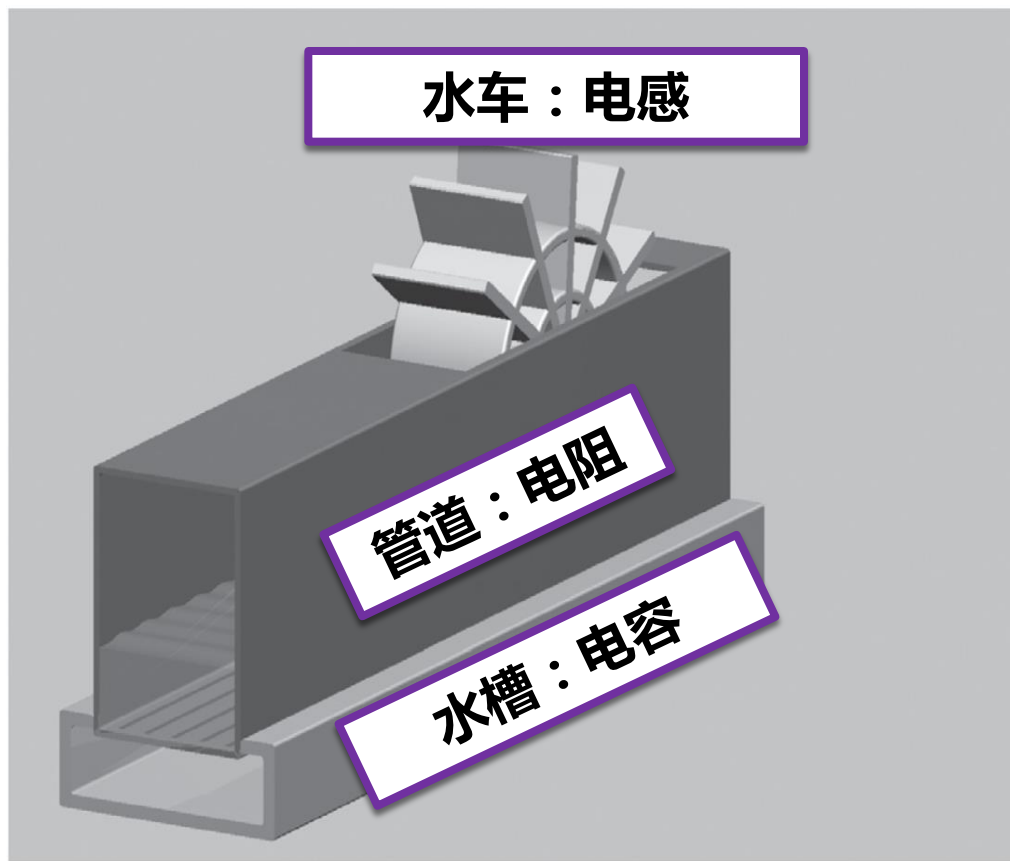




# 功耗是最关键问题



# 导线延时 (Wire Delay)






金属线变细：

电阻  $R$  

电容  $C$  

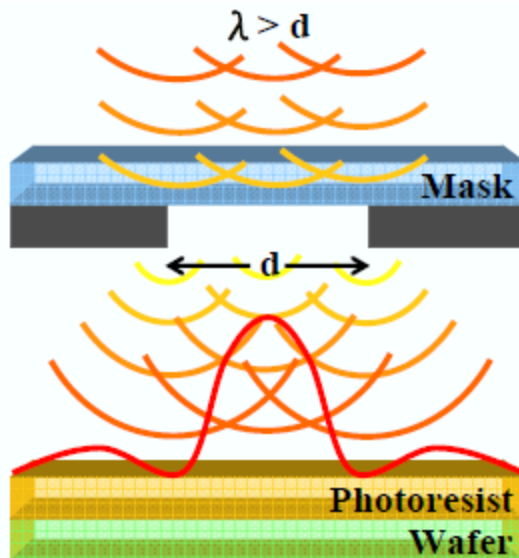
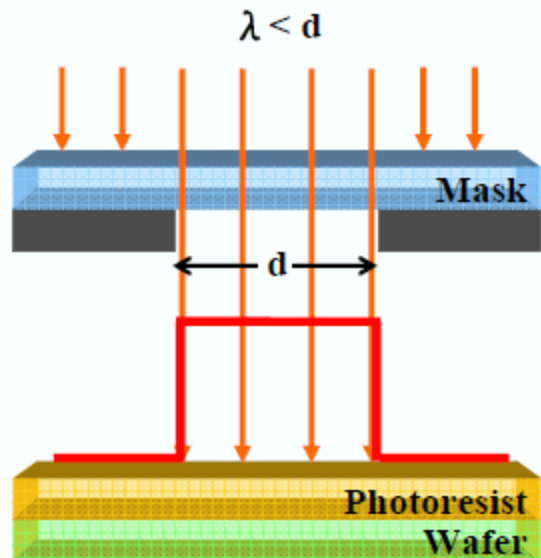
$$\text{延时 } D = R \times C$$

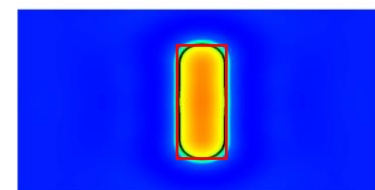
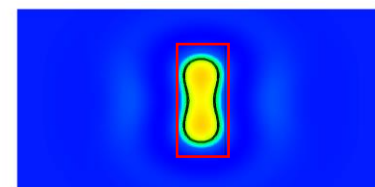
电阻增大速度远大于电容减少速度！



# 可制造性问题

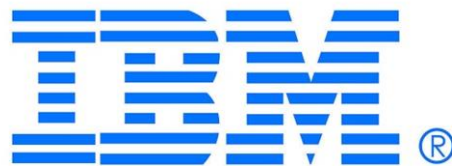


- 良片率
- 193nm vs. 40nm, 28nm, 16nm
- OPC (光学邻近校正技术), Multiple Patterning Lithography
- 极紫外光刻 (10+nm)





# 大公司的游戏



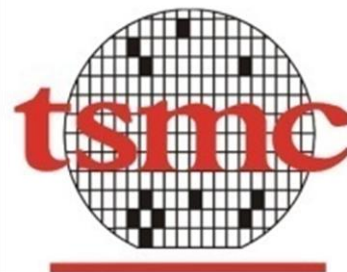
16nm  
12-15B \$



22nm  
8-10B \$



32nm  
5-7B \$



45nm  
3.5-5B \$



三星电子



# 现代半导体行业



投资

技术、器件和电路  
创新，系统集成

超越摩尔定律

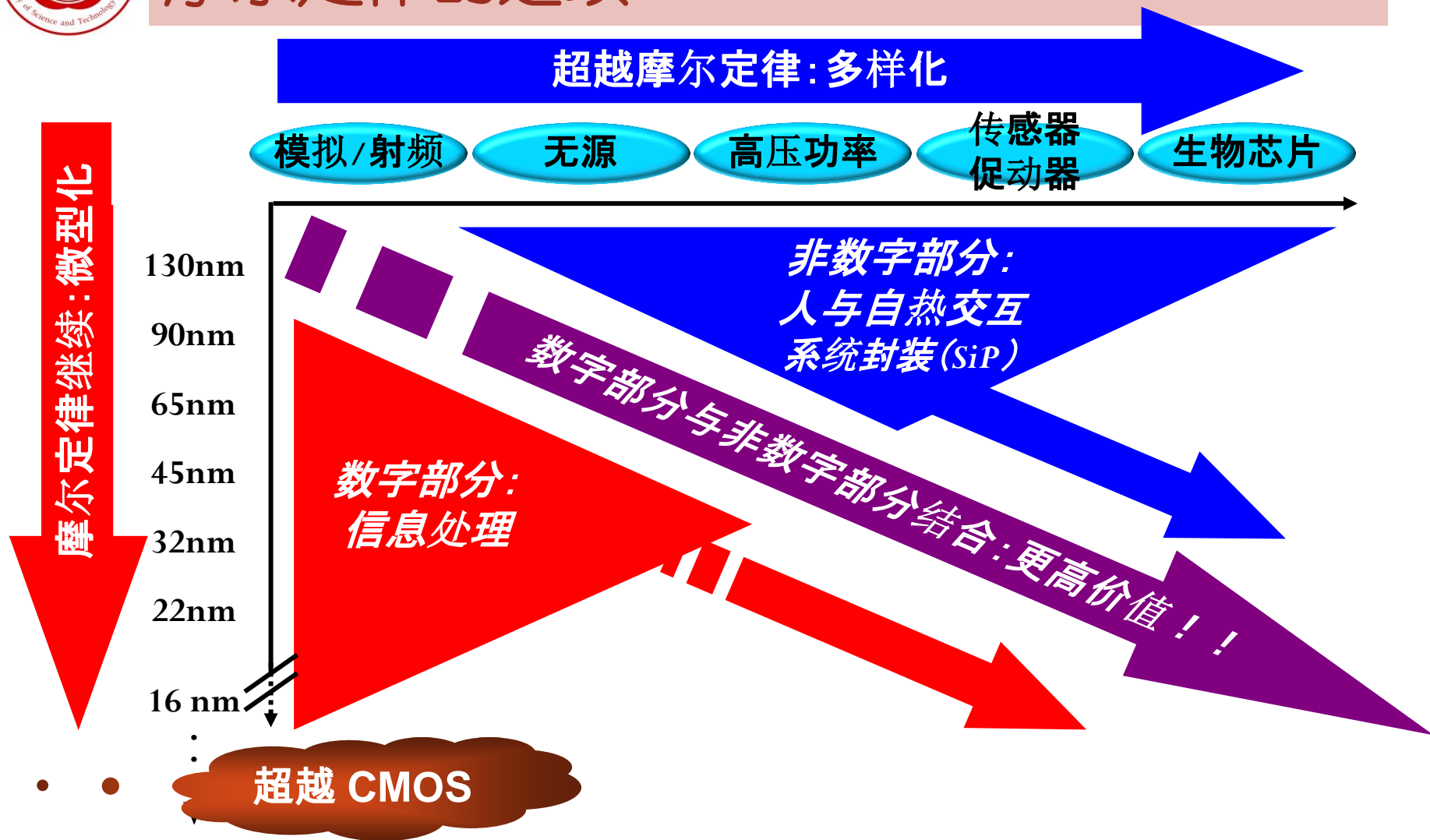
功能增强  
和/或  
成本更低

市场增长





# 摩尔定律的延续

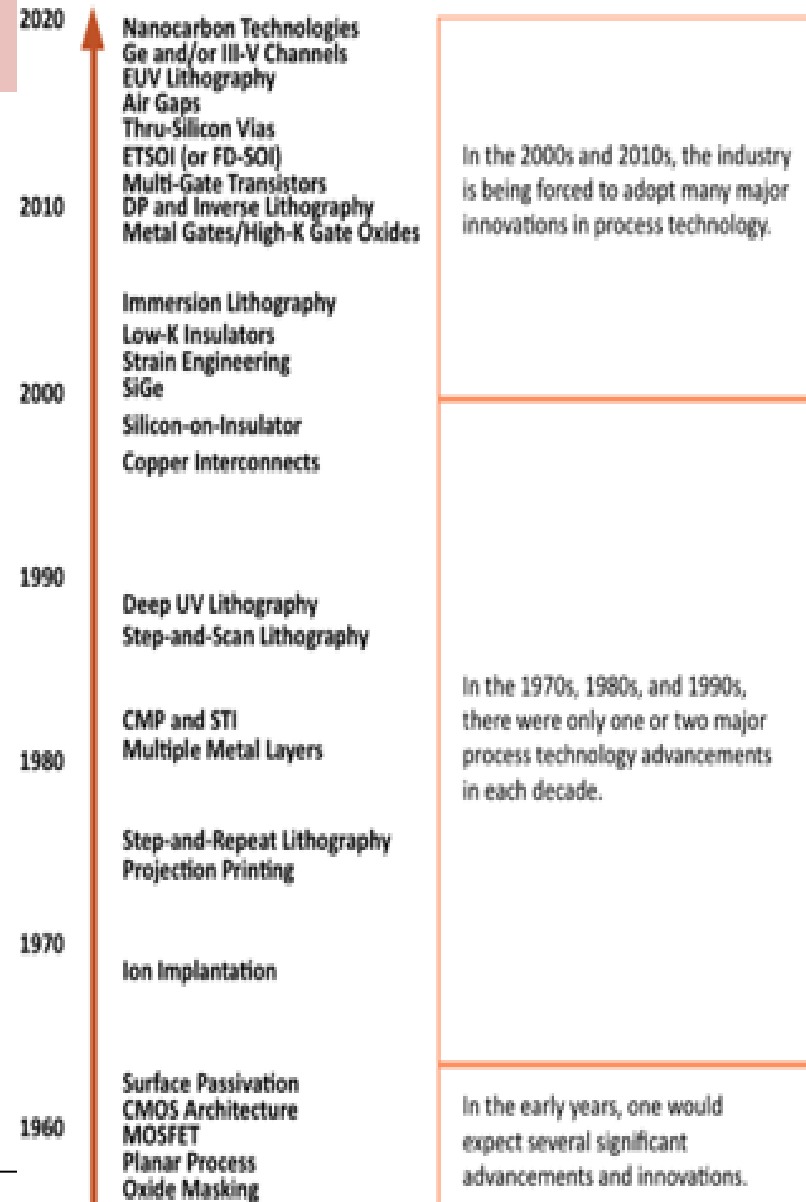




# Technology Trends

- Advanced lithography methods needed to continue shrinking chip geometries
- New interconnect schemes
- Strain engineering for improved performance and lower power consumption
- 3D integration
- Novel transistor structures
- Migration to larger wafers

## Major Process Technology Innovations Are Piling Up





# 提纲



## 集成电路



## Golden Moore & Von Neumann



## 纳米电子时代的挑战



## 集成电路设计



# Integrated Circuits Industry

## Design(设计)

**Tools & IP:** Synopsys, Cadence, Mentor Graphics, etc.

**Fabless:** Qualcomm, MediaTek, Huawei (华为), Xilinx, Altera, Spreadtrum (展讯), etc.



## Wafer Manufacturing (晶圆制造)

**Lithography Instruments:** ASML, NEC, etc.

**Foundries:** TSMC, UMC, GF, Intel, Samsung, SMIC (中芯国际)



## Packaging & Testing (封装与测试)

**Testing Instruments :** Agilent (安捷伦), Rohde&Schwarz

ASE Global, Amkor, etc.



# ASIC (专用集成电路)

## Design Automation

System/Behavioral  
Descriptions

**High-level Synthesis**  
高层次综合

Scheduling;  
Binding;  
Allocation.

Register Transfer Level  
Descriptions

**Logic Synthesis**  
逻辑综合

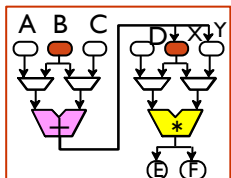
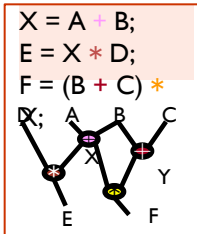
Logic  
Optimization  
;  
Technology  
Mapping.

Gate Level Netlist

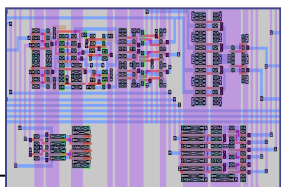
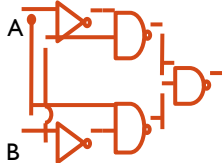
**Physical Synthesis**  
物理综合/  
芯片版图

Floorplanning;  
Placement;  
Routing;  
etc.

Layout mask



Adder 1 Multiplier 1  
Register 8 Multiplexer 4







# High-level Synthesis (高层次综合)

- Transformation from a behavioral specification of a system to its RTL structure specification
  - E.g., from C/C++ to RTL, Bluespec, Xilinx AutoESL
  - Promote the productivity
  - Essential tasks: scheduling, binding, allocation

begin

```
done = 0; A = inA; B = inB;
```

```
while ( !done )
```

```
begin
```

```
  if ( A < B )
```

```
    swap = A;
```

```
    A = B; B = swap;
```

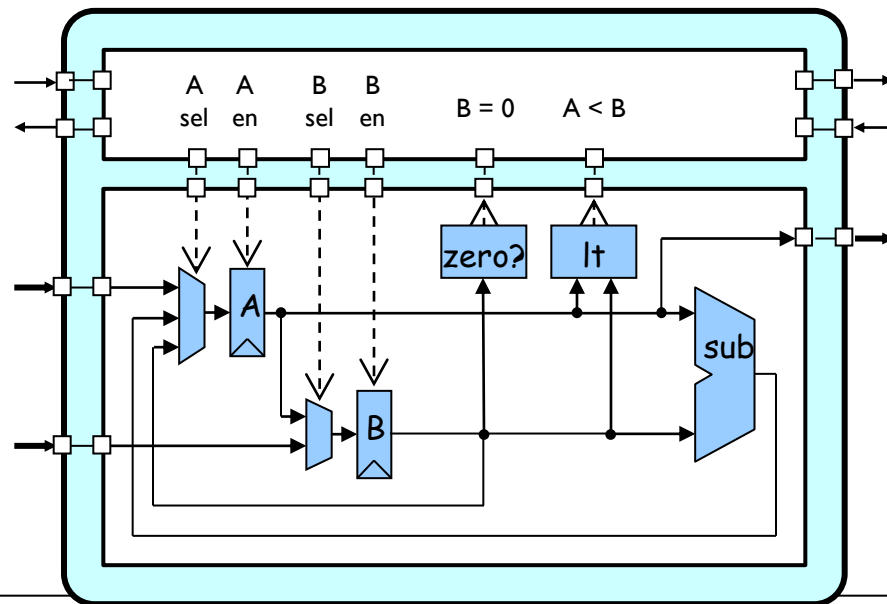
```
  else if ( B != 0 )
```

```
    A = A - B;
```

```
  else
```

```
    done = 1;
```

```
end
```





# Logic Synthesis (逻辑综合)

- Transformation from a Register-Transfer-Level (RTL) description to a gate-level netlists
  - Hardware Description Language
    - Verilog HDL, VHDL
  - Logic Optimization
  - Technology Mapping



# Physical synthesis(物理综合)

- Transformation from a gate-level netlists to its physical layouts (masks)
  - Partitioning (划分)
  - Floorplanning (布图规划)
  - Power/Ground Network Synthesis (电源线/地线网络合成)
  - Placement (布局)
  - Routing (布线) : Clock Tree, Signal, Power/Ground
  - Post-routing (后布线优化)
    - Redundant Via Insertion (Design for Yield)

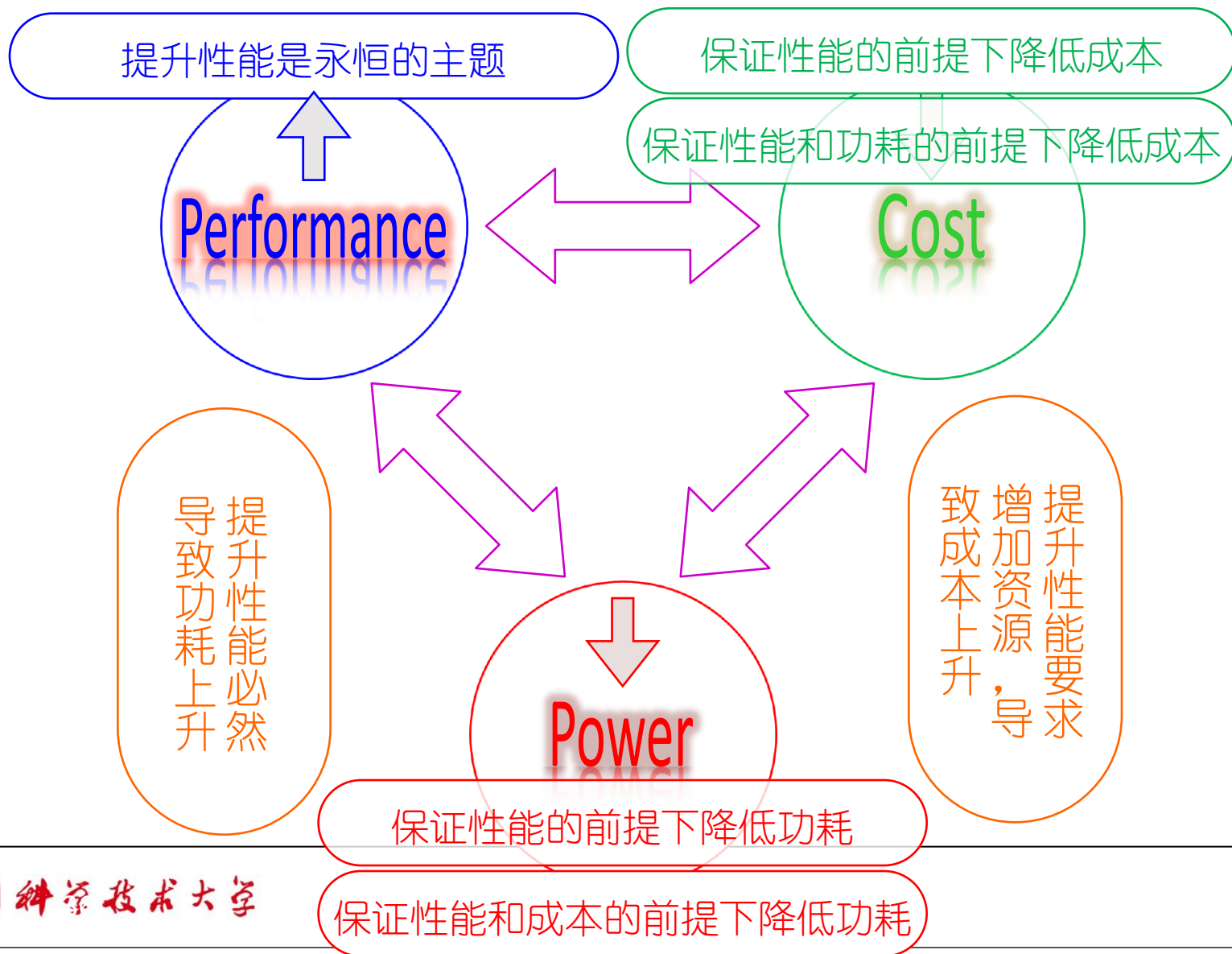
**Large Scale Discrete Optimization Problems:**

**Computation-Consuming.**

**How to find good solutions in acceptable time?**



# Performance, Power, Cost





# Modern Chip (VLSI) Design

- Managing Design Complexity (设计复杂性)
  - System-on-Chip: IP reuse, Platform-based Design Methodology
  - Electronic System Level Synthesis (High-level synthesis)
    - Raising the design abstraction
- Power (功耗)
  - Low Power Technologies: Leakage Power, Dynamic Power
  - New Device: FinFET
- Interconnect (互连)
  - Delay, System-level design & Physical Design
  - Network-on-Chip
  - 3D ICs
  - Optical-/wireless-/CNT-/RF Interconnect
- Reliability (可靠性)
- Design For Manufacturability: EUV, OPC, PSM, ...